

NOV 21 2005

PATENT

Atty. Dkt. No. APPM/007034.P1/DSM/LOW K/JW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Yim, et al.

Serial No.: 10/773,060

Confirmation No.: 5473

Filed: February 4, 2004

For: Ultra Low Dielectric Materials
Based on Hybrid System of Linear
Silicon Precursor and Organic
Porogen by Plasma-Enhanced
Chemical Vapor Deposition
(PECVD)

Group Art Unit: 1762

Examiner: Marianne L. Padgett

MAIL STOP AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450CERTIFICATE OF FACSIMILE
TRANSMISSION UNDER 37 CFR 1.8I hereby certify that this correspondence and the documents
referred to as attached therein are being facsimile transmitted to
the U.S. Patent and Trademark Office to the fax number
indicated by the Examiner, namely, fax number (571) 273-8300
to the attention of the named Examiner, on the date below.

11/21/05

Date

Signature

Dear Sir:

SECOND RESPONSE TO FINAL OFFICE ACTION DATED AUGUST 26, 2005

In response to the Final Office Action dated August 26, 2005, having a shortened statutory period for response set to expire on November 26, 2005, please enter this response and reconsider the claims pending in the application for reasons discussed below. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/APPM/007034.P1/KMT for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Claims are listed beginning on page 2 of this paper. Remarks begin on page 5 of this paper.